



SHEET 1 OF 1

Form PTO 1449
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PATENT AND TRADEMARK OFFICE

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10/802,836

LIST OF REFERENCES CITED BY APPLICANT

APPLICANT

Yukio TANIGUCHI, et al.

FILING DATE

March 18, 2004

GROUP

U.S. PATENT DOCUMENTS

EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
	AA						
	AB						
	AC						
	AD						
	AE						
	AF						
	AG						
	AH						
	AI						
	AJ						
	AK						
	AL						
	AM						
	AN						

FOREIGN PATENT DOCUMENTS

		DOCUMENT NUMBER	DATE	COUNTRY	TRANSLATION	
					YES	NO
	AO					
	AP					
	AQ					
	AR					
	AS					
	AT					
	AU					

OTHER REFERENCES (Including Author, Title, Date, Pertinent Pages, etc.)

RK	AV	Chang-Ho OH, et al., Japan Journal of Applied Physics, vol. 37, pages L492-L495, "A NOVEL PHASE-MODULATED EXCIMER-LASER CRYSTALLIZATION METHOD OF SILICON THIN FILMS", May 1, 1998
RK	AW	M. NAKATA, et al., The Japan Society of Applied Physics, vol. 40, part 1, no. 5, pages 3049-3054, "A NEW NUCLEATION-SITE-CONTROL EXCIMER-LASER-CRYSTALLIZATION METHOD", May 2001
RK	AX	M. MATSUMURA, IDW '02 AMD5-1, pages 263-266, "ADVANCED LASER-CRYSTALLIZATION TECHNOLOGIES OF Si FOR HIGH-PERFORMANCE TFTs", 2001
RK	AY	International Display Workshops, pages 1-6, "ADVANCED LASER-CRYSTALLIZATION TECHNOLOGIES OF Si FOR HIGH-PERFORMANCES TFTs" (with partial English translation)
RK	AZ	Journal of The Surface Science Society of Japan, vol. 21, no. 5, pages 278-287, "PREPARATION OF ULTRA-LARGE GRAIN SILICON THIN-FILMS BY EXCIMER-LASER", 2000 (with partial English translation)

☐ Additional References sheet(s) attached

Examiner /Robert Kunemund/

Date Considered 07/21/2006

*Examiner: Initial if reference is considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.